

2025 NNCI Etch Symposium

The Demands on Plasma Etching: Challenges and Solutions

June 30 – July 2, 2025
Massachusetts Institute of Technology
Cambridge, MA
Jointly hosted by Harvard CNS and MIT.nano

NNCI is an NSF-sponsored network comprising 16 sites and nearly 30 university-shared research facilities across the United States. The network fosters collaboration through events that bring together technical experts in specific fabrication disciplines. The primary goal of the 2025 NNCI Etch Symposium is to provide a platform for researchers to share collective knowledge on innovative processes for addressing challenges for etching novel materials and shapes. This focused symposium also offers valuable opportunities to network with leading experts in the field.

This event will feature scientific and technical presentations, vendor exhibitions, student poster sessions, and panel discussions. Expert speakers in plasma etching and nanofabrication will discuss the challenges in plasma etching.

Please visit the [2025 NNCI Etch Symposium website](#) for registration, accommodations, and updated information.

Call for Participation

If you are interested in presenting a poster or giving a presentation, please see the [call for abstracts for details](#).

Important dates

- Registration and Abstract Submission Opens: **February 10, 2025**
- Abstract Submission Deadline: **March 31, 2025**
- Acceptance Notifications: **April 20, 2025**
- Exhibition Application Deadline: **May 30, 2025**
- Registration Deadline: **June 16, 2025**

If you have any questions, please direct them to any member of the organizing committee.

Organizing Committee

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